

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant | : | Ogata et al. |
| Appl. No. | : | 10/588,866 |
| Filed | : | August 9, 2006 |
| For | : | POLYMER COMPOUND, PHOTORESIST COMPOSITION INCLUDING THE POLYMER COMPOUND, AND RESIST PATTERN FORMATION METHOD |
| Examiner | : | Walke, A. |
| Group Art Unit | : | 1795 |

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **September 22, 2008**, please consider the following remarks.

The listing of claims begins on page 2 of this paper. No amendments have been made.

Remarks begin on page 4 of this paper.